

Safety and behaviour in the cleanroom



Safety and behaviour in the cleanroom

- What is a cleanroom ?
- CMi cleanroom concept
- CMi User Manual
- Working in CMi cleanroom
- Safety at CMi
- Multi choice questions test to fill at your convenience (10min)
- Visit of the cleanroom (10h30 or 14h00)





Video credits: EPFL CMi

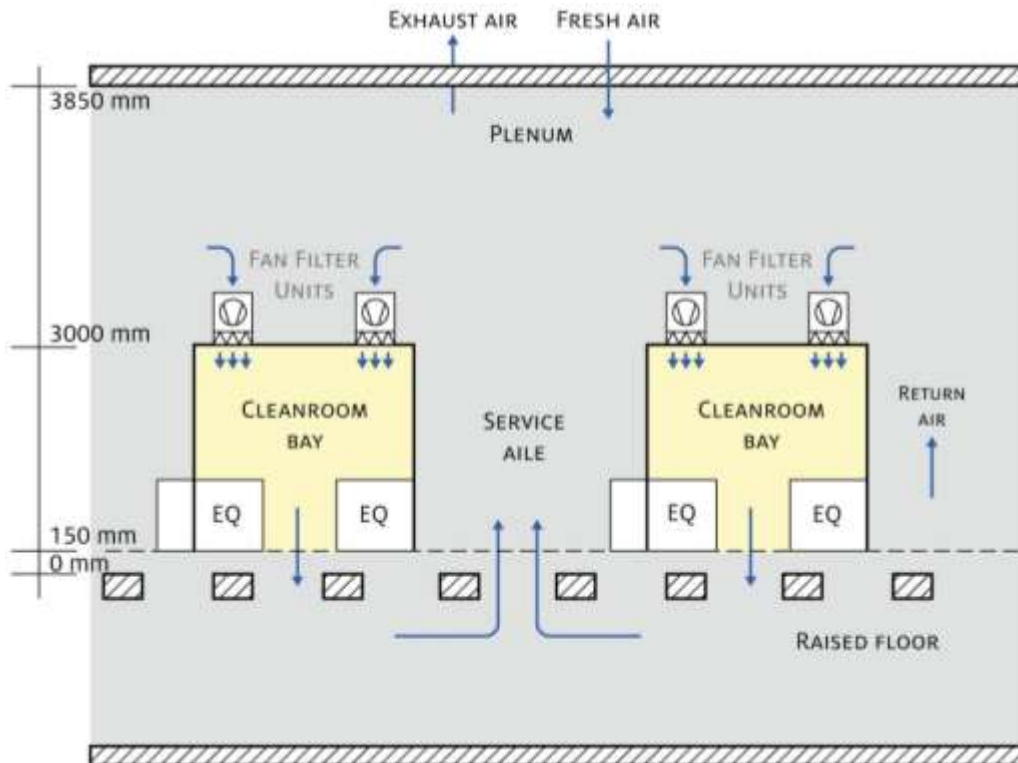
What is a cleanroom ?



What is a cleanroom?

1

- Continuous air supply through filters. Laminar flow top to bottom.
- Tight control of working conditions (temp, humidity, UV-light)



FRESH AIR

- 60'000 m³/h
- filter efficiency: 99.97% for particles size: 0.1-0.3 μ m

EXHAUST

- 36 '000 m³/h

FFU

- 0.7 m² active area
- filter efficiency : 99.999% for particles size 0.1-0.3 μ m

What is a cleanroom?

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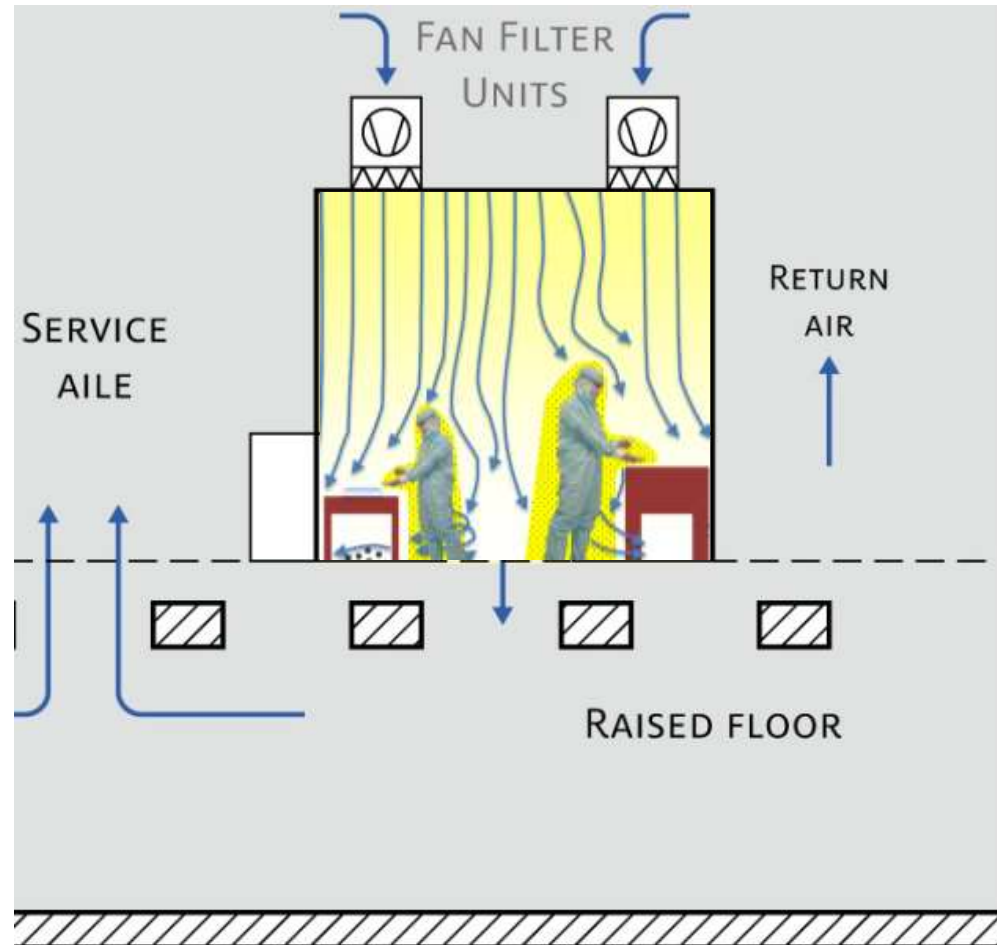
- Continuous air supply through filters. Laminar flow top to bottom.
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What is a cleanroom?

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- Continuous air supply through filters. Laminar flow top to bottom.
- Tight control of working conditions (temp, humidity, UV-light)



What is a cleanroom?

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- Tight control of media:
 - Water (minerals, particles, dissolved ions)
 - Chemicals (purity, mobile ions)
 - Gas (purity, water vapor content, particulates)



What is a cleanroom?

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Concentration max allowed of particles (particles/m³ of air)

Particles sizes equal or superior to that given below

(0.5µm
particles/ft³ of air)

Class ISO	0.1 µm	0.2 µm	0.3 µm	0.5 µm	1 µm	5 µm	Class US FS209
ISO 1	10	2	0	0	0	0	
ISO 2	100	24	10	4	0	0	
ISO 3	1 000	237	102	35	8	0	1
ISO 4	10 000	2 370	1 020	352	83	0	10
ISO 5	100 000	23 700	10 200	3 520	832	29	100
ISO 6	1 000 000	237 000	102 000	35 200	8 320	293	1 000
ISO 7	∞	∞	∞	352 000	83 200	2 930	10 000
ISO 8	∞	∞	∞	3 520 000	832 000	29 300	100 000
ISO 9	∞	∞	∞	35 200 000	8 320 000	293 000	

CMi BM -1



CMi BM +1



Standard ISO 14644-1

What is a cleanroom?

1

Cleanroom environment requires special cloth, compatible tools, lint free paper.

- Body may contaminate by:

Flakes of dead skin

Hair

Touch by hand

Breathing

- Wrong cloth may release:

Fibers

Dust

- Wrong tools may create:

Particles

Dust

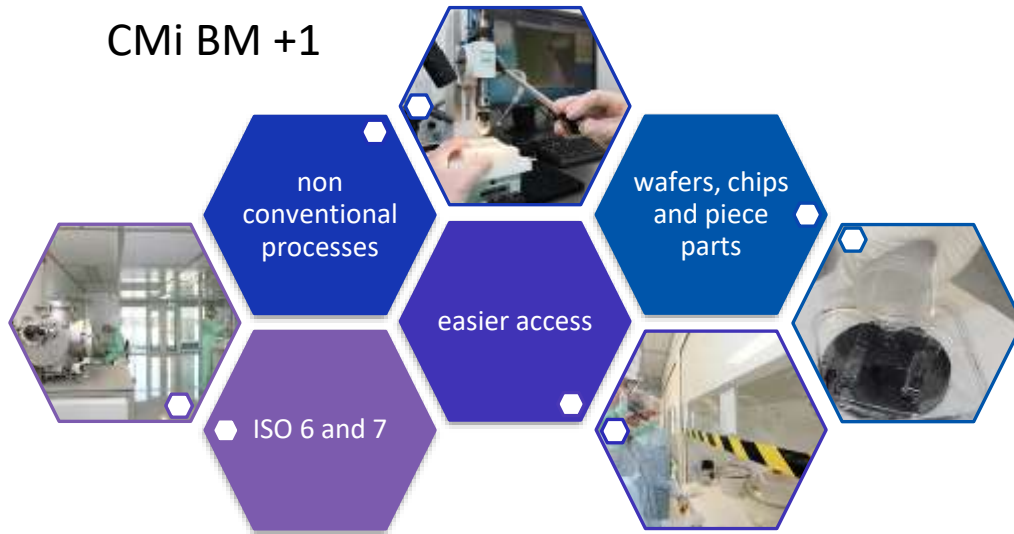




CMi cleanroom concept

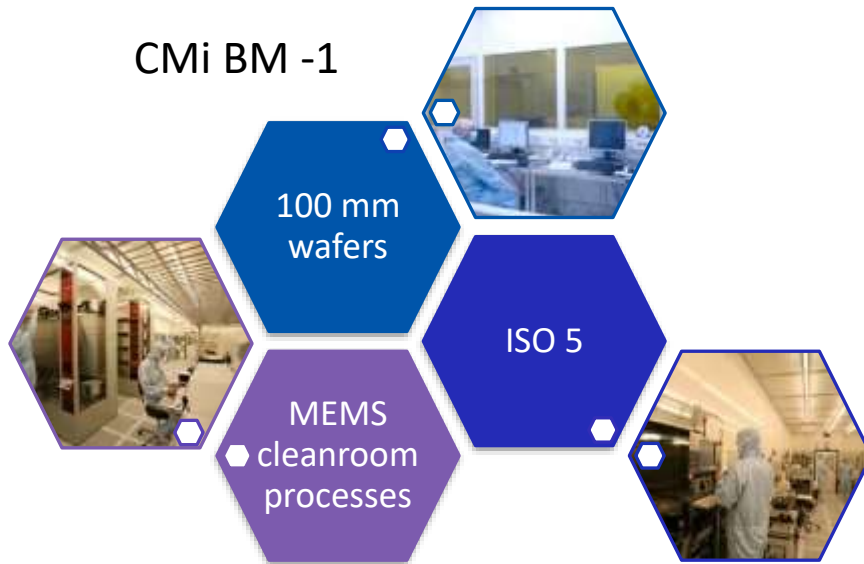
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CMi BM +1



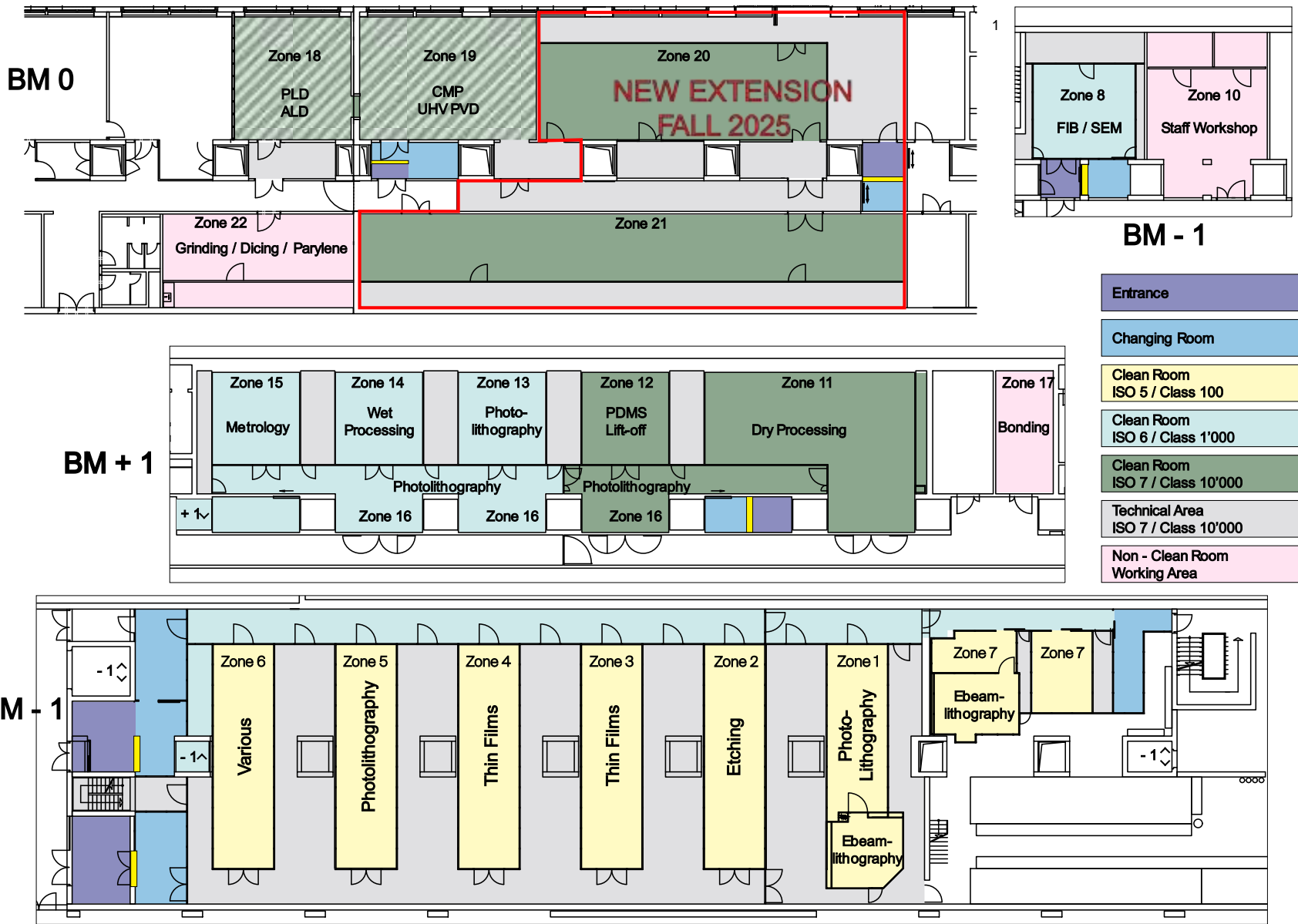
Grinding
Thermal imprint
IBE
PDMS line
Photolithography on chips
Customized chemistry
Metrology

CMi BM -1



Ebeam lithography
DUV lithography
Photolithography
Etching plasma and wet
Thins films (LPCVD, oxidation, CVD, ALD)
Metrology

CMi cleanroom concept

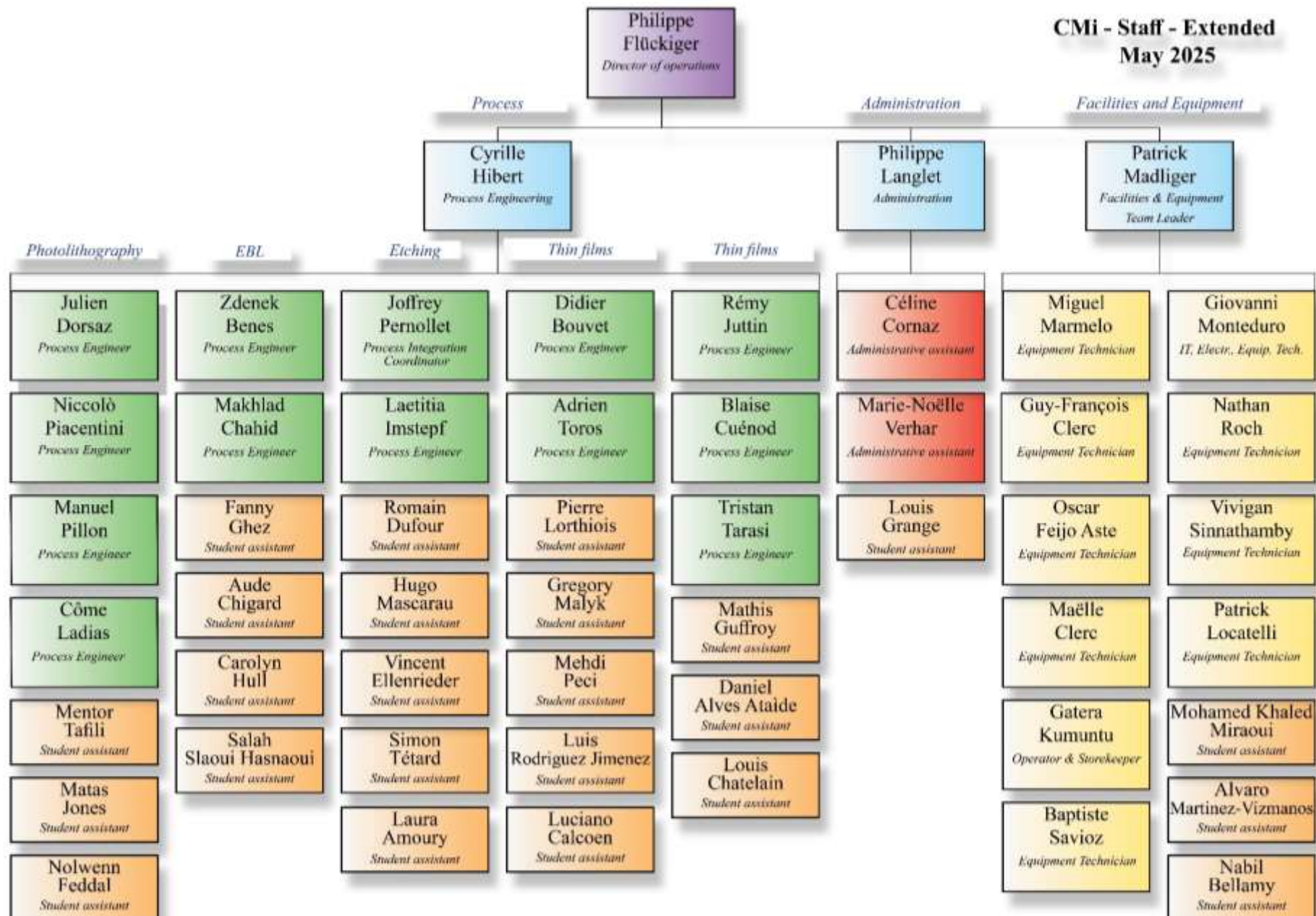


Access to zones 18-19-22 during extension work

1







CMi user manual: step by step

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1. Safety and behaviour in the cleanroom (now)

- Formal presentation of CMi facilities and CMi rules
- Cleanroom visit
- Email from CMi secretary with **process flow template + MCQ test link**



2. Project approval by CMi process engineers (~1 week)

- You send a process flow or a draft to infocmi@epfl.ch
- Process flow review by a technical committee
- Email from CMi secretary (username, password)

11	Process flow - design Machine: All or Direct laser + AC/DC Mask: CD = 100 Device size: 100	
12	Dry film - Back film Material: 100 Machine: DPT Depth: 1.2 µm	
13	Acid layer Material: 100 Machine: DPT Depth: 1.2 µm	
14	STP film - Back film Material: 100 Machine: DPT Depth: 1.2 µm	

3. Start working in the cleanroom (few weeks)

- Trainings
- Rights to book equipment
- Work on your own according to process flow (reservation, login, processing, logout...)










CMi user manual: process flow

Process flow work

1. Process flow template
2. User's modification
3. Process flow sent to CMi
4. Technical committee if necessary
5. Process flow correction
6. Process flow final review by CMi
7. Process flow accepted

Lab:	Phone:	
Operator Name:	Office:	
Supervisor Name:	E-mail:	

07	<i>Photolith expo + develop</i> Machine: <i>direct laser IV + ACS200</i> Mask: <i>CD = 20 µm</i> Align: <i>tol: 1.5 µm</i>	
08/09	<i>Metal Evaporation + lift-off</i> Machine: <i>LAB600H</i> Metal: <i>Ti / Au</i> Thickness: <i>10 / 60 (nm)</i> + Solvent - sonication	
10	<i>Photolith PR coat</i> Machine: <i>ACS200</i> PR: <i>AZ1512 - 2.0 µm</i>	
11	<i>Photolith expo + develop</i> Machine: <i>M4 or Direct laser + ACS200</i> Mask: <i>CD = 20µm</i> <i>Double side align</i>	
12	<i>Dry Etch - Back Side</i> Material: <i>SiO2</i> Machine: <i>SPTS</i> Depth: <i>0.5 µm</i>	
13	<i>Resist Strip</i> Material: <i>AZ1512 - 1.1µm</i> Machine: <i>Tepla + Remover</i>	
14	<i>KOH Etch - Back Side</i> Material: <i>Si</i> Machine: <i>KOH Wetbench</i> Depth: <i>325 µm</i>	

CMi user manual: practical training, feedback and CMi annual review

1

Training on equipment

- Usually one person at a time
- On your wafers in process (no dummies)
- On the agreed technology
- Limited to the necessary equipment agreed
- Justified only for long term projects
- Planned according to staff availability
- Use training request program

Users feedback to CMi staff

- Modify or adjust technology when problem occurs
- CMi memory
- Improve CMi offer

CMi annual review

- Next one is **13th May 2025**
- Each User must provide a poster
- CMi booklet (poster collection)
- Conferences, poster session, food and drinks ☺



CMi user manual

CMi web site

<https://cmi.epfl.ch/>

+ fees

+ training request

+ visit authorisation

+ my bill

Browse Research Use our infrastructure Center of MicroNanotechnology

Center of MicroNanotechnology

Reservations

Organisation

Equipment

Process

Center of MicroNanotechnology

The CMi is a complex of clean rooms and processing equipment for the training and scientific experimentation devoted to the users of microtechnologies.



CENTER OF MICRONANOTECHNOLOGY CMi

SPIDER 800
DÉPÔT PAR PULVÉRISATION
Table des matières

- I Introduction
- II Principe de fonctionnement
- III Caractéristiques techniques
- IV Sécurité d'utilisation
- V Maintenance



Equipment
user manual

Systeme matri: Accepted

Control des reservations

Systeme matri: Accepted

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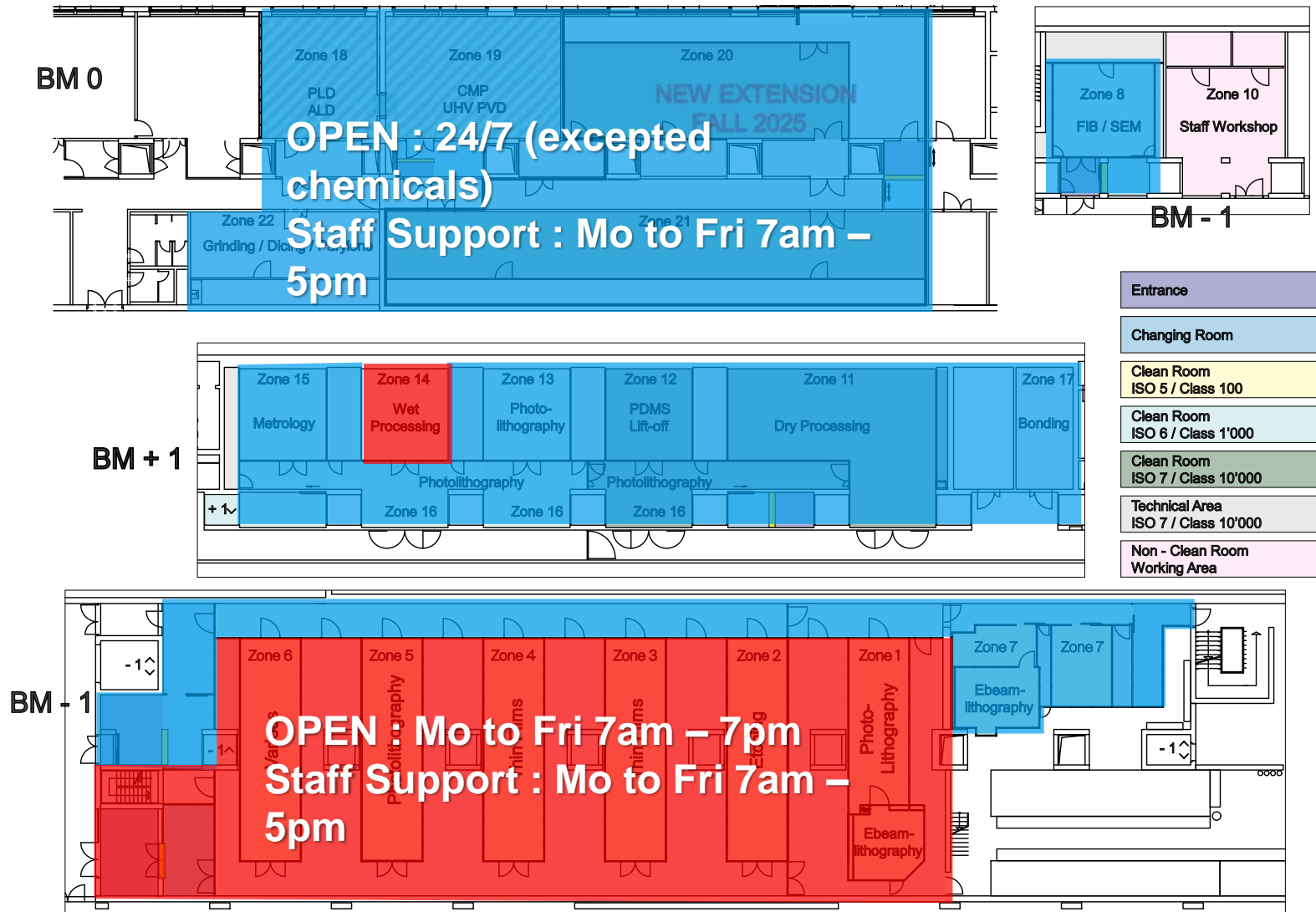
Systeme matri: Accepted

Control des reservations

System

CMi user manual: working hours & staff support

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CMi user manual: working hours & staff support

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- Work **prohibited** after 7pm
- Few exceptions on critical tools for **advanced users on request**
- Staff support from Monday to Friday 7am to 5pm



- Access 24h/7 days **on request**
- Staff support from Monday to Friday 7am to 5pm
- Lone worker device to wear from **7pm to 7am**



Lone worker devices in the BM+1 entrance

CMi user manual: fees

Academics

(Practical training, Semester & Master students, PhD students and Researchers)

Tools are charged per run and usage time,
Hourly rate depends on tools (see table),
Materials and consumables are charged.
Manual tools: metals and
PDMS charged separately.

Companies

Hourly fees (see table).

Categories	EPFL		Swiss Academics		International Acad.		Industry	
	CHF/run	CHF/hour	CHF/run	CHF/hour	CHF/run	CHF/hour	CHF/run	CHF/hour
E-Beam Writer & DUV Stepper	30.00	46.00	36.00	55.20	48.00	74.00	80.00	207.00
Packaging	30.00	46.00	36.00	55.20	48.00	74.00	80.00	81.00
Laser Writer & Mask Aligner	15.00	34.00	18.00	40.80	24.00	54.00	32.00	86.00
Coater Developer (Auto)	15.00	113.00	18.00	135.60	24.00	181.00	32.00	205.00
Coater Developer (Manual)	15.00	113.00	18.00	135.60	24.00	181.00	32.00	199.00
Dry Etcher	15.00	40.00	18.00	48.00	24.00	64.00	32.00	99.00
LPCVD, ALD, PVD	15.00	63.00	18.00	75.60	24.00	101.00	32.00	133.00
Thermal Process	15.00	28.00	18.00	33.60	24.00	45.00	32.00	65.00
Wet bench	15.00	37.00	18.00	44.40	24.00	59.00	32.00	70.00
Measurement tools	15.00	18.00	18.00	21.60	24.00	29.00	32.00	40.00
Other Tools	3.00	12.00	3.60	14.40	5.00	19.00	6.00	26.00

➤ All rates (machines, reservation fees, consumables) are available on your CMi user account.

Problem on a processing equipment

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General rules:

- Check **after each process step** that you got your desired results.
- **Report** any defects or problem **immediately** to the staff in charge of the equipment.

What to do in case of problem on a processing equipment:

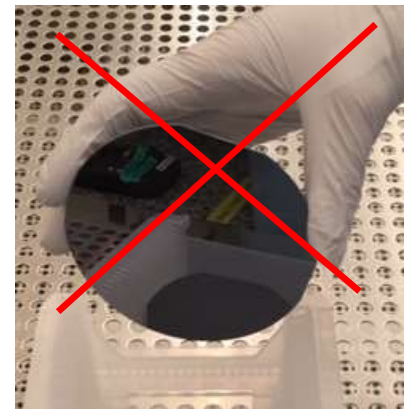
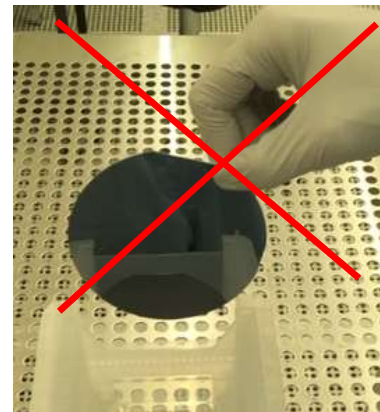
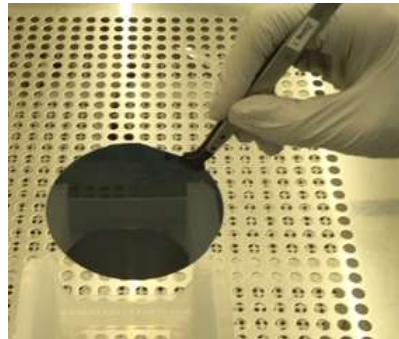
1. The user immediately **reports to CMi staff** so the concerned equipment can be checked and preventively put to maintenance state.
2. The user **sends an email** to the staff member in charge the same day with:
 - a. User login
 - b. Machine
 - c. Date
 - d. Time
 - e. Related process flow document mentioning the concerned process step
 - f. If possible, a picture of the sample
 - g. The requested adjustment of the invoice
3. The user transmits the sample to the staff in charge for inspection.
4. If applicable, the user checks the ongoing invoice that agreed refund is effective, before the billing at the end of the month.

Invoice / Billing:

- **Any complaint about an invoice**, concerning or not defective process or equipment, **must be addressed to CMi within 24h** (one business day).
- CMi may refund the cost concerning a process step, but will not refund the cost of all proceeding process steps, nor the cost of lost samples.
- Users are asked to **regularly check** their current month's invoice, and to address to CMi any request for corrections **before the billing at the end of the month**.
- **Once** the final invoice is **issued**, no request for refund can be treated and **no modifications are possible**.

Cleanroom general rules

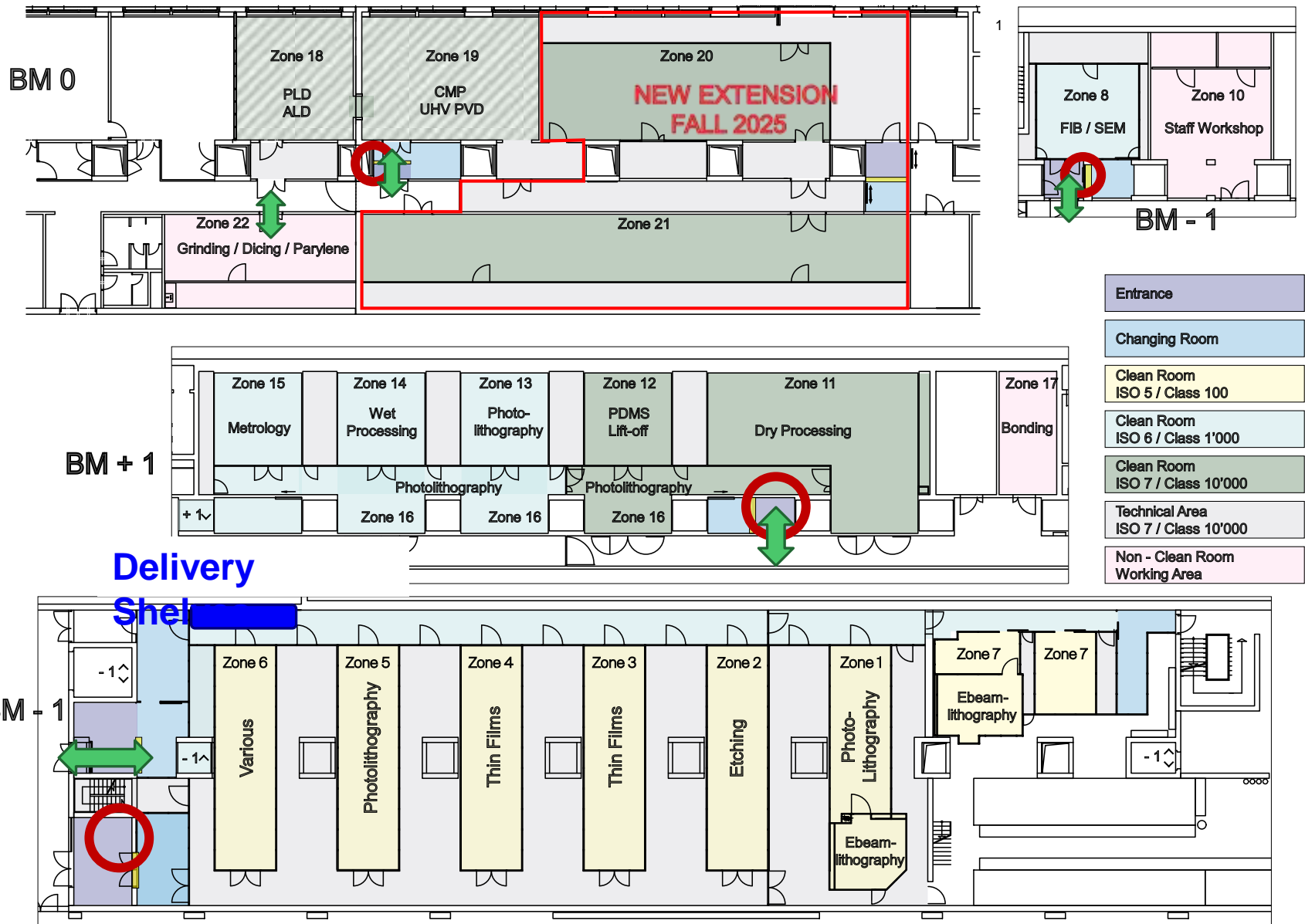
- Material should be stored in labelled basket
- All wafers should be stores in boxes
- Every item (Wafer Box / Tweezer box etc) has to be **properly labelled with username and lab/company.**
- **Black Boxes** stays in the BM-1 Cleanroom !
- Lost and found shelf
- Good Working Practice (GWP): wafers/samples **must** be handled with vacuum or mechanical tweezers



Entering CMI cleanroom



Accesses, main delivery place and material introduction into cleanroom



Enter only through entrance specified in your authorization email. Exit only through the same entrance you used for entry.

CMI ENTRY procedure

**IF YOU HAVE ANY SYMPTOMS OF FLU
DO NOT ENTER CLEANROOM !!!**

1. (Disinfect your hands)



2. Put on new clean white face mask.



3. Put on blue shoe cover and pass the bench.



4. Put on hair net.



5. Put on your private suit from your locker.



6. Put on boots.
Boots are shared.



7. Put on your personal safety or medical glasses.



8. Put on the gloves.



9. Check everything again.
You should look like this.
Enter the cleanroom.

CMI EXIT procedure

1. Remove boots and put them back on the shared shoe shelf.



2. Trash your gloves and remove your suit and place it and your glasses in your locker.



3. Remove hair net and trash it.



4. Cross over the bench and trash the blue shoe covers.



5. Pick your stuff from the locker, if you used it.



6. Exit cleanroom.



Material introduction into cleanroom

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- All material introduced in CMi cleanroom:
 - Must be announced to infocmi@epfl.ch for the first time
 - Must be decontaminated:
 - in dedicated material room for BM -1
 - in dressing room for BM +1 and FIB room
- Outside the cleanroom: **decontamination**
 1. Put on gloves.
 2. Wipe with IPA.
 3. Place inside the cabinet, on appropriate shelf.
 4. Get dressed to access the cleanroom.
 5. Collection from inside the cleanroom.



Operate the other way around to get the material out.

Mobile phone policy

No phones in processing area !

You may:

- Use an earpiece headset, (only 1 allowed, no listening to music in cleanroom!)
- Or go in the dressing room (acceptable solution).
- Or go to grey area (best solution),

1



Remark: staff may use mobile phones in the processing area for alarms and repairing/diagnosing tools.
Not a privilege but an exception!

Safety at CMI



Safety rules: general

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CAMIPRO required for each person entering or leaving the cleanroom

Never work alone: a buddy is required in the cleanroom at all times

Only one emergency phone number :

115

(021 693 3000)

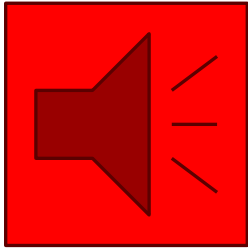
(from mobile phone)

Report any safety problems you encounter

Wear protective glasses or medical glasses all the time

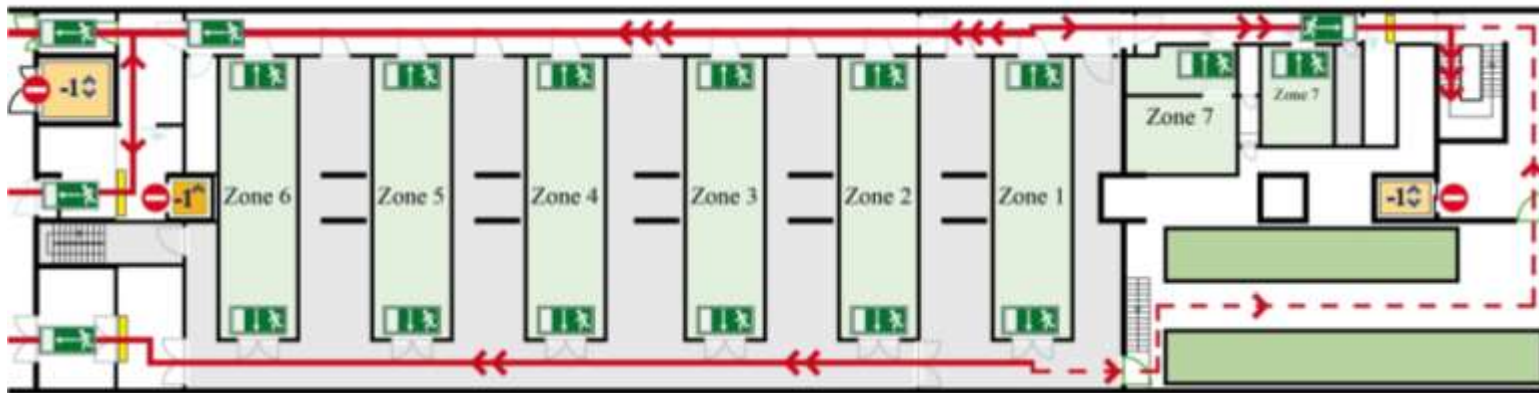
Safety rules: alarms & Evacuation in CMi BM -1 / Z18-19

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Double tone horn

Flashing red light

→ Evacuate immediately with cleanroom clothingToxic gas
Fire

Meeting point : BM 1.124 (CMi secretariat office)
wait there to be accounted for

Remark : red alarm can be activated by the push-buttons

Safety rules: chemicals and trash

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NO CHEMICALS in personal lockers or in personal storing baskets!!!



Dedicated bins for Silicon wafers and other glass parts
NEVER trash sharp objects in regular bin with plastic bag



Safety rules: chemistry

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- INFORM yourself (SDS).
- Do NOT crowd fume hoods/wet benches!
- Only ONE user at a time for “strong” chemistry (concentrated acids/bases).
- Do NOT stress operator for quick finish.
- Finish clean and safe (workplace, bottles, wares...)

Extra dressing

- nitrile gloves
- safety apron
- face shield
- long gloves



EPFL Center of MicroNanoTechnology

Product: **Trimethylchlorosilane (TMCS)**User name: **Joffrey Pernollet**Creation Date: **February 18, 2011**Review Date: **Not yet done****IMPORTANT NOTE**

This document is a standard operation procedure. It is not a substitute of the Material Safety Data Sheet (MSDS). Therefore, it is strongly advised to refer with great attention to the MSDS of the product before going further.

☐ Filled by the user

☐ Filled by the CMI staff

1. Standard Operation Procedure**1.1. Procedure name and description****SOP name:** TMCS anti-sticking

This product is mainly used in PDMS casting processes as a surface conditioning treatment to prevent sticking between piece parts which come to contact for molding purposes but which need, in the end, to be easily separated from each other. Proceed on the dedicated wet bench as point out below.

- Put on single use additional gloves.
- Fetch the TMCS bottle in the "solvent" cabinet located on the right side of the wet bench.
- Place 2 or 3 drops of TMCS in the small glass receptacle located in the glass desiccator (single use pipettes are available for that purpose).
- Place the silicon/SUS mold in this very same desiccator.
- Close the desiccator and place it under vacuum (this causes the TMCS to evaporate and to form a passivation layer on the mold surface).
- Close the TMCS bottle and put it back in the "solvent" cabinet. **Fill in the "chemicals follow-up" document.**
- When desired time is reached, vent the desiccator once. **DO NOT** open it yet. Put it back under vacuum for a while so all TMCS vapors are suck away.
- Vent it and open it. **DO NOT** breath directly above the open desiccator.
- Take your mold back and close the desiccator.

1.2. Working hours restrictions

Allowed under "strict buddy rule". A buddy may be any authorized user of the clean room in visual contact with the authorized user. Strictly apply personal protective behavior of point 2.4.

EPFL Center of MicroNanoTechnology

1.3. Storage Location

TMCS bottle is located in Z12, in the "solvent" cabinet on the right side of the PDMS wet bench.

Carefully close any open container and store it vertically to prevent any flow in case of leakage. **DO NOT** rinse with water.

1.4. Recycling procedure

Dedicated recycling container is located in zone 12, by the TMCS desiccator on the wet bench.

2. Safety**2.1. Material Safety Data Sheet: see concerned document****2.2. Hazards associated to the chemical (choose according to MSDS)****2.3. Risk and Safety phrases**

R11 Easily flammable
R14 Reacts violently to water contact
R35 Provokes serious burns

2.4. Protective behavior and equipment needed**Respiratory protection**

Always wear the clean-room facial mask. Do not breathe vapors, gases. Ensure correct ventilation, manipulate under a venting hood.

Hands protection

In addition to the standard clean-room gloves, always manipulate using extra single-use gloves.

Eyes protection

Always wear the clean-room safety glasses.

Safety rules: chemistry

Chemicals use authorization - CMI

Specific CAMIPRO access for:

- **HF** Hydrofluoric Acid
- **HNO₃** Nitric Acid
- **TMAH**
Tetramethylammonium Hydroxide
- Mixtures

This paper must be signed by all cleanroom users working in zone 14 (BM 1.116) with one or more chemicals (included mixtures) mentioned below:

Please check the appropriate box.

- ACID - Hydrofluoric acid (HF)
CAS number: **7664-39-3**

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- ACID - Nitric acid (HNO₃)
CAS Number: **7697-37-2**

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- BASE - Tetramethylammonium hydroxide (TMAH)
CAS Number: **75-59-2**

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The signing person hereby confirms to have read the MSDS of these chemicals (available here <https://cmiaccess.epfl.ch/restricted>) and understood risks. The user also commits to respect CMI Safety rules and never provide these chemicals to someone else.

When requested, CMI commits to give access to the above-mentioned chemicals stored under lock.

Date

Name user (in block letters please)

Lab / Compagny

Signature user

Signature CMI staff - Etching Dept

Cleanroom tour

Thank you for your attention.

Now is the moment to ask questions, to share observations and to make comments.

You can download these slides :

<https://www.epfl.ch/research/facilities/cmi/organisation/how-to-be-a-member-of-cmi/>

Next steps:

1. cleanroom tour
2. fill CMi form
3. answer multi question test
4. submit a process flow to infocmi for approval

